

Thermal Oxidation Furnace (Ultra Clean Samples)

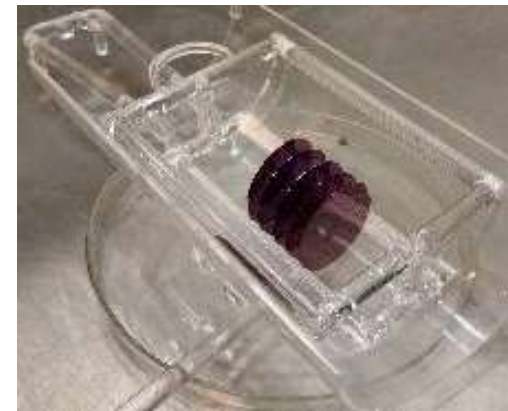
▪ *Dry Oxidation:*

- Samples : up to 4" wafers
- Gases : N_2 , O_2
- Temperatures : 400°C to 1050°C
- Oxide Thickness Minimum : 1 nm



▪ *Wet Oxidation:*

- Samples : up to 4" wafers
- Gases : N_2 , O_2
- Temperatures : 900°C and 1050°C
- Oxide Thickness Minimum : 10 nm



Wet Oxidized wafers